

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :

Hatakeyama et al.

Group Art Unit: TBA

Serial No.: TBA

Examiner: TBA

Filed: November 28, 2001

For: AMINE COMPOUNDS, RESIST COMPOSITIONS AND PATTERNING PROCESS

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend the claims as follows:

9. (Amended) A process for forming a resist pattern comprising the steps
of:

applying the resist composition of claim 5 onto a substrate to form a
coating,

heat treating the coating and then exposing it to high-energy radiation having a
wavelength of less than 300 nm or electron beams through a photo mask, and
optionally heat treating the exposed coating and developing it with a developer.

REMARKS

The Commissioner is hereby authorized to charge any fees associated with this response or credit any overpayment to Deposit Account No. 13-3402.

Respectfully submitted,



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Attorney Docket No.: KOJIM-436

Date: November 28, 2001

VERSION WITH MARKINGS TO SHOW CHANGES MADE

IN THE CLAIMS:

Please amend the claims as follows:

9. (Amended) A process for forming a resist pattern comprising the steps of:

applying the resist composition of claim 5 [or 6] onto a substrate to form a coating,

heat treating the coating and then exposing it to high-energy radiation having a wavelength of less than 300 nm or electron beams through a photo mask, and

optionally heat treating the exposed coating and developing it with a developer.